DECLARATION

I hereby declare that the entire work embodied in the thesis entitled “Ultrathin Diffusion Barrier Layers for Copper Metallization in Silicon Based Integrated Circuits” is the result of investigation carried out by me in the Department of Electronic Science, Kurukshetra University Kurukshetra under the joint supervision of Dr. Mukesh Kumar, Assistant Professor, Department of Electronic Science, Kurukshetra University, Kurushetra and Prof. Dinesh Kumar, Professor, Department of Electronic Science, Kurukshetra University, Kurushetra.

I also declare that this thesis has not been earlier submitted elsewhere for any degree or diploma. In keeping with the general practice, due acknowledgments have been made wherever the work described is based on finding of other investigators. Any omissions that might have occurred due to oversight or error in judgment are regretted.

Sumit Sharma